

FORM PTO-1449
U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE
LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)

ATTORNEY DOCKET NO. 4704/USA/ETCH/SILICON
APPLICANT: Yuen et al.
FILING DATE: Herewith

SERIAL NO.:
1763
GROUP: Unk.

09-718,319
SHEET 1 OF 5
U.S. PTO
JC914 11/21/00
09/718319

U.S. PATENT DOCUMENTS

Examiner Initial		DOCKET NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING IF APPROPRIATE
<i>gag</i>	A1	4	2	8	2	2	6	7	08/04/81	Koyel	427	38	_____
	A2	4	4	3	3	2	2	8	02/21/84	Nishimatsu, et al.	219	10.55 R	_____
	A3	4	4	6	5	5	3	2	08/14/84	Fukano	156	643	_____
	A4	4	4	9	0	2	0	9	12/25/84	Hartman	156	643	_____
	A5	4	5	0	2	9	1	4	03/05/85	Trumpp et al.	156	643	_____
	A6	4	5	7	6	6	9	2	03/18/86	Fukuta, et al.	204	165	_____
	A7	4	7	0	5	5	9	5	11/10/87	Okudaira et al.	156	643	_____
	A8	4	7	3	8	7	4	8	04/19/88	Kisa	156	643	_____
	A9	4	7	8	6	3	5	2	11/22/88	Benzing	156	345	_____
	A10	4	8	1	8	3	2	6	04/04/89	Liu, et al.	156	345	_____
	A11	4	8	3	1	9	6	3	05/23/89	Saito, et al.	118	723	_____
	A12	4	8	6	3	5	6	1	09/05/89	Freeman, et al.	156	646	_____
	A13	4	8	6	7	8	4	1	09/19/89	Loewenstein, et al.	156	643	_____
	A14	4	8	7	6	2	1	2	10/24/89	Koury	437	34	_____
	A15	4	9	7	5	1	4	4	12/04/90	Yamazaki, et al.	156	643	_____
	A16	4	9	9	2	1	3	6	02/12/91	Tachi et al.	156	643	_____
	A17	4	9	9	4	4	1	0	02/19/91	Sun et al.	437	192	_____
	A18	5	0	0	2	6	3	2	03/26/91	Loewenstein, et al.	156	643	_____
	A19	5	0	1	3	3	9	8	05/07/91	Long et al.	156	643	_____
	A20	5	0	3	5	7	6	8	07/30/91	Mu et al.	156	626	_____
	A21	5	0	8	4	1	2	6	01/28/92	McKee	156	345	_____
	A22	5	0	9	4	7	1	2	03/10/92	Becker et al.	156	643	_____
	A23	5	1	1	0	4	0	8	05/05/92	Fujii et al.	156	643	_____
	A24	5	1	1	0	4	1	1	05/05/92	Long	156	656	_____
	A25	5	1	1	8	3	8	7	06/02/92	Kadomura	156	657	_____
	A26	5	1	5	8	6	4	4	10/27/92	Cheung, et al.	156	643	_____
	A27	5	1	6	0	4	0	7	11/03/92	Latchford et al.	156	656	_____
	A28	5	1	6	4	3	3	0	11/17/92	Davis et al.	437	192	_____
	A29	5	1	7	6	7	9	2	01/05/93	Followan et al.	156	652	_____
	A30	5	1	8	8	9	8	0	02/23/93	Lai	437	193	_____
	A31	5	1	9	2	7	0	2	03/09/93	Tseng	437	47	_____

EXAMINER

George Souldren

DATE CONSIDERED

10-021

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

09-718319 SHEET 3 OF 5

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE								ATTORNEY DOCKET NO. 4704/USA/ETCH/SILICON		SERIAL NO.: N/A		
		LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)								APPLICANT: Yuen et al.		1763		
										FILING DATE: Herewith		GROUP: Unknown		
FOREIGN PATENT DOCUMENTS														
		DOCKET NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
<i>gpgy</i>	B1	0	2	7	2	1	4	3	06/22/88	EP Application				
	B2	0	3	1	4	9	9	0	05/10/89	EP Application				
	B3	0	4	6	3	3	7	3	01/02/92	EP Application				
	B4	0	5	1	6	0	4	3	12/02/92	EP Application				
	B5	0	5	5	5	5	4	6	08/18/93	EP Application				
	B6	0	6	9	7	4	6	7	02/21/96	EP Application				
	B7	0	7	4	6	0	1	5	12/04/96	EP Application				
	B8	4	1	3	2	5	5	9	04/08/93	German Application				
	B9	9	6	1	5	5	4	5	05/23/96	PCT				
	B10	6	1	7	7	0	9	2	06/24/94	Japan				
<i>gpgy</i>	B11	7	0	2	9	8	7	9	01/31/95	Japan				
EXAMINER	<i>George Goudreau</i>								DATE CONSIDERED 10-02-1					
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.														

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE							ATTORNEY DOCKET NO. 4704/USA/ETCH/SILICON		SERIAL NO.: N/A
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Yuen et al.									
		FILING DATE: Herewith							GROUP: U <u>1763</u>		

U.S. PATENT DOCUMENTS

Examiner Initial		DOCKET NUMBER					DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<i>gsg</i>	A32	5	2	5	6	2	4	Keller, et al.	156	643		
	A33	5	2	8	1	3	0	Gabric, et al.	156	643		
	A34	5	2	8	2	8	9	Balmashonov, et al.	118	723 R		
	A35	5	3	1	2	5	1	Sakai, et al.	134	1		
	A36	5	3	1	8	6	6	Tamaki, et al.	156	662		
	A37	5	3	3	8	3	9	Szwejkowski, et al.	156	655		
	A38	5	3	5	4	4	1	Cheung, et al.	156	643		
	A39	5	3	5	6	4	7	Chen, et al.	134	1		
	A40	5	3	5	8	6	0	Cathey	156	656		
	A41	5	3	7	8	3	1	01/03/95	Nagayama, et al.	156	643	
	A42	5	3	8	2	3	1	Hills, et al.	156	643		
	A43	5	4	1	3	9	5	Aydil, et al.	437	81		
	A44	5	4	3	1	7	7	Babie, et al.	156	643.1		
	A45	5	4	4	3	6	8	Jones, et al.	216	37		
	A46	5	4	4	9	4	1	09/12/95	Fukuda, et al.	118	723 MP	
	A47	5	5	1	4	6	2	05/07/96	Bornstein, et al.	437	189	
	A48	5	5	2	1	1	1	05/28/96	Chen, et al.	437	187	
	A49	5	5	2	9	1	9	06/25/96	Grewal	216	68	
	A50	5	6	2	0	6	1	04/15/97	Keller	438	720	
	A51	5	6	2	6	7	7	05/06/97	Roberts, et al.	216	67	
	A52	5	6	4	4	1	5	07/01/97	Keller	257	324	
	A53	5	7	5	3	5	3	05/19/98	Saito	437	192	
	A54	5	7	5	6	4	0	05/26/98	Ye, et al.	438	710	
	A55	5	7	6	7	0	2	06/16/98	Imai, et al.	438	719	
	A56	5	7	8	8	7	9	08/04/98	Steger, et al.	156	345	
	A57	5	8	4	3	2	3	12/01/98	Shrotriya	134	1.1	
	A58	5	8	6	6	4	8	02/02/99	Shiau, et al.	438	720	
	A59	5	8	6	9	4	0	02/09/99	Brunemeier, et al.	438	710	
	A60	5	8	7	4	3	6	02/23/99	Hoh, et al.	438	721	
<i>gsg</i>	A61	5	8	7	9	5	7	03/09/99	Tepman, et al.	216	68	

EXAMINER

*George Souldreau*DATE CONSIDERED *10-02-01*

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

09-718319 SHEET 4 OF 5

FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTORNEY DOCKET NO. 4704/USA/ETCH/SILICON	SERIAL NO.: N/A
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Yuen, et al.	
		FILING DATE: Herewith	GROUP: 1763

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

C1	Aydil, et al., "Multiple Steady States in a Radio Frequency Chlorine Glow Discharge," <u>J. Appl. Phys.</u> , Volume 69, No. 1, January 1, 1991, pages 109-114		
C2	Hillenius, S.J., et al., "A Symmetric Submicron CMOS Technology," <u>IEEE</u> , pages 252-255, 1986		
C3	PCT Search Report dated October 28, 1999.		
C4	PCT Notification of International Search Report dated February 4, 1999		
C5			
C6			
C7			
C8			
C9			
C10			
C11			
C12			
C13			
C14			
C15			
C16			
C17			
C18			
C19			
C20			
EXAMINER	George Gould reau	DATE CONSIDERED	10-02

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

PENDING U.S. PATENT APPLICATIONS

ATTORNEY DOCKET NO.: 4704/USA/ETCH/SILICON
 SERIAL NUMBER: N/A
 FILING DATE: HEREWITH
 INVENTORS: YUEN, ET AL.

09-718,319

1763

EXAMINER INITIAL		PENDING U.S. PATENT APPLICATIONS
<i>Gong</i>	D1	U.S. Patent Application entitled, "Method for Improved Cleaning of Substrate Processing System"; filed July 11, 1997; Serial No. 08/893,922; Inventors: Kao, et al.
	D2	U.S. Patent Application entitled, "Apparatus for Improved Remote Microwave Plasma source for Use with Substrate Processing Systems"; filed April 23, 1997; Serial No. 08/839,111; Inventors: Kao, et al.
	D3	U.S. Patent Application entitled, "Method and Apparatus for Determining the Endpoint in a Plasma Cleaning Process"; filed July 2, 1997; Serial No. 08/887,165; Inventors: Subrahmanyam, et al.
	D4	U.S. Patent Application entitled, "Apparatus and Method for Efficient and Compact Remote Microwave Plasma Generation"; filed April 22, 1997; Serial No. 08/839,007; Inventor: Bhatnagar
	D5	U.S. Patent Application entitled, "Method and Apparatus for Pre-stabilized Plasma Generation for Microwave Clean Applications"; filed November 13, 1996; Serial No. 08/746,658; Inventors: Fong, et al.
	D6	U.S. Patent Application entitled, "Inductively Coupled HDP-CVD Reactor"; filed May 29, 1997; Serial No. 08/865,018; Inventors: Redeker, et al.
	D7	U.S. Patent Application entitled, "Symmetric Tunable Inductively Coupled HDP-CVD Reactor"; filed July 15, 1996; Serial No. 08/679,927; Inventors: Redeker, et al.
	D8	U.S. Patent Application entitled, "Apparatus and Methods for Upgraded Substrate Processing System with Microwave Plasma Source"; filed March 5, 1997; Serial No. 08/811,627; Inventors: Tanaka, et al.
<i>Gong</i>	D9	U.S. Patent Application entitled, "Microwave Apparatus for In-situ Vacuum Line Cleaning for Substrate Processing Equipment"; filed October 30, 1996; Serial No. 08/741,241; Inventors: Pang, et al.
	D10	
	D11	
	D12	
	D13	
	D14	<i>George Gunderson 10-02</i>